

	Hits	Search Text	DBs
1	1	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((mask or reticle or photo\$3mask\$4) same pattern\$4) and ((project\$4 or imping\$4 or bombard\$4) same (plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 alkane) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
2	1	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((project\$4 or imping\$4 or bombard\$4) same (plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 alkane) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
3	31	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 (methane or ethane or alkane)) or \$5fluoro\$3methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
4	34	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near9 (methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	0	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((mask or reticle or photo\$3mask\$4) same pattern\$4) and ((project\$4 or imping\$4 or bombard\$4) same (\$4beam or plasma or e\$3beam or (electron near4 beam) or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near5 alkane) or \$5fluoro\$3methane))	USOCR

	Hits	Search Text	DBs
6	1	((projection or lithographic) same (apparatus or system)) and ((radiation or light or optical) same (source or system)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or (\$3halogen\$5 near9 (methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask)	USOCR

	Hits	Search Text	DBs
7	28	((radiation or light or optical or projection or lithographic) same (source or system or apparatus) same (substrate or wafer or device or workpiece) same (support or stage or hold) same (pattern or mask or reticle or photomask)) and ((plasma or beam or (electron near beam) or RF or (electromagnetic near field) or (plasma near source) or laser or IAD or ion assist dep or EUV or DUV or beam) same ((fluoro near carbon) or carbon fluoride or carbon chloride or (halogen near (methane or ethane or alkane)) or fluoro methane))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	6	((("6252648") or ("20020000519") or ("6268904") or ("4987008") or ("6407385") or ("20020051124"))).PN.	US-PGPUB; USPAT

	Hit s	Search Text	DBs
9	128	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
10	85	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane) same gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB



	Hits	Search Text	DBs
11	1	<p>(projection near9  \$5lithograph\$4 near9 (system  or apparatus)) and ((radiation  or light or optical or laser  or project\$4 or  \$4lithograph\$6) same (source  or system or apparatus)) and  ((substrate or wafer or device  or workpiece) same (support\$3  or stage or hold\$3)) and  pattern\$4 and ((plasma or  e\$3beam or (electron near4  beam) or beam or RF or  (electro\$3magnetic near6  field) or (plasma near5  source) or EUV or DUV) same  ((fluoro near6 carbon) or  carbon\$6fluoride or  carbon\$6chloride or  ((\$3halogen\$5 or fluor\$4)  near9 (hydrocarbon or methane  or ethane or alkane)) or  \$5fluoro\$3methane)) and  ((pattern\$6 near5 device) or  mask\$4 or reticle or  photo\$4mask) and (gas\$3 same  (plasma or ion\$3beam or beam  or laser or ion\$4assist\$5)  same (nitrogen or hydrogen or  ammonia or NH\$3 or diazene or  hydrazine or (nitric near5  acid)))</p>	<p>US-PGPUB;  USPAT; EPO;  JPO;  DERWENT;  IBM_TDB</p>

	Hits	Search Text	DBs
12	4	<p>(projection near9 (optical or \$5lithograph\$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))</p>	<p>US-PGPUB;  USPAT; EPO;  JPO;  DERWENT;  IBM_TDB</p>

	Hits	Search Text	DBs
13	2	<p>(projection near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))</p>	<p>US-PGPUB;  USPAT; EPO;  JPO;  DERWENT;  IBM_TDB</p>

	Hits	Search Text	DBs
14	6	(projection near9 (optical or system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	55	((light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3) same ((pattern\$4 near9 device) or mask or photomask or reticle)) and ((plasma or e\$3beam or (electron near4 beam) or beam or (electro\$3magnetic near6 field) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitrogen or hydrogen or ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
16	29	((light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3) same ((pattern\$4 near9 device) or mask or photomask or reticle)) and ((plasma or e\$3beam or (electron near4 beam) or beam or (electro\$3magnetic near6 field) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	41	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (ammonia or NH\$3 or diazene or hydrazine or (nitric near5 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	0	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitric near5 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB



	Hits	Search Text	DBs
19	0	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitr\$4 near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	18	((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) same ((fluoro near6 carbon) or carbon\$6fluoride or carbon\$6chloride or ((\$3halogen\$5 or fluor\$4) near9 (hydrocarbon or methane or ethane or alkane)) or \$5fluoro\$3methane)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitr\$4 near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
21	57	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus) same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (nitric near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	2	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus) same ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5) near9 ((HNO\$2 or nitric) near8 acid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
23	111	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal)) and pattern\$4 and (plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((plasma or ion\$3beam or beam or laser or ion\$4assist\$5) near9 ((HNO\$2 or nitric) near8 acid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB